

RESEARCH ARTICLE

Fabrication and Characterization of Silicon Quantum Dots Thin Films for Optoelectronic Applications

Aditya Srivastava, Shamshad A. Khan, Archana Srivastava*

ABSTRACT: Silicon quantum dots (Si-QDs) have garnered significant attention due to their tunable optical and electronic properties, making them ideal candidates for optoelectronic devices, including solar cells. In this study, we synthesized thin films of Si-QDs with a thickness of 20 nm on quartz substrates using a physical vapor deposition method under varying substrate temperatures (165 K, 135 K, and 115 K) and a constant argon gas pressure (4 Torr). The structural, optical, and electrical properties of the Si-QDs were extensively characterized to assess their potential in optoelectronics. X-ray diffraction (XRD) analysis revealed the amorphous nature of the synthesized quantum dots, with no sharp crystalline peaks detected, indicating nanoscale dimensions. Field Emission Scanning Electron Microscopy (FESEM) and High-Resolution Transmission Electron Microscopy (HRTEM) imaging confirmed quantum dot sizes ranging from 3-7 nm, with well-dispersed nanoparticles forming a uniform thin film. Optical properties were analyzed using UV-Visible spectroscopy, which demonstrated a distinct absorption edge corresponding to a direct band gap, suggesting strong quantum confinement effects in the Si-QDs. The optical band gap varied slightly depending on the deposition temperature, indicating temperature-dependent quantum dot size control. Electrical measurements were conducted through temperature-dependent DC conductivity (I-V-T) analysis, which revealed an exponential increase in conductivity with rising temperature, confirming the semiconducting behavior of Si-QDs. These results underscore the potential of Si-QDs as high-efficiency materials for optoelectronic devices, particularly in solar cell applications, due to their direct band gap, high absorption coefficient, and favorable electrical conductivity.

Keywords: Silicon Quantum Dots (Si-QDs), Optoelectronic Devices, Thin Films, Electrical Properties, DC Conductivity.

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1. INTRODUCTION

In the present nanotechnology world, Si is one of the most dominant material for optoelectronic devices. To fabricate functional devices, it is important to understand the electrical, optical, and other characteristics of Si quantum dots in detail. The Si quantum dots have unique properties, such as their use in new-generation solar cells [1, 2]. The synthesis of quantum dot Solar cells (QDSSCs) is easy and it has a wider band gap semiconductor electrode, sensitizer, counter electrode, and

redox electrolyte [3]. These solar cells have fascinated researchers due to various advantages such as cheap production cost, tuned bandgap according to size because of the quantum confinement effect over traditional solar cells [4, 5]. Because of these reasons, the semiconductor QDs can enhance the power conversion efficiency of solar cells. Since quantum dots offer large optical band gaps and the band gap governs the absorption wavelength of quantum dots [6]. The highly efficient QDSSCs have a striking influence in the power generation field during this time of energy crisis. This will also reduces the emission of greenhouse gases [7]. The span of the collected solar spectrum will decide the conversion efficiency of solar cells. Generally, a huge portion of the solar spectrum is lost in the IR and UV ranges. In solar cell materials, the ultraviolet photons create hot electrons

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which are thermalized due to the coupling of phonons. These thermalized electrons do not constitute current. Due to these electrons, the temperature of solar material increases as well as efficiency decreases. Among various inorganic materials studied for solar cells so far, the use of Silicon quantum dots is of utmost importance and increases the power conversion efficiency [8]. The Silicon quantum dots are the perfect nanomaterial for solar cell usage with proven quantum characteristics and properties [9, 10]. The Si quantum dots are stable besides soaking of light and high absorption constant in comparison to other forms of Silicon. So, due to these unique and extraordinary properties, Si quantum dots are chosen by the researchers for the exploration about the best candidate as the solar cell material. Researchers are hopeful about pavement of striking and new path in the Si based advanced solar cell technology.

One can easily control the physical properties of nanomaterial by adjusting size of the particle. The semiconductor quantum dots (QDs) consists quantum confinement effect and got widespread attention due to their contemporary technical and scientific uses [11]. These quantum dots are assuring candidates due to their outstanding optical and electrical parameters which can be easily optimized based on choice of required device [12]. In recent years, it has been found that Si nanostructures are applicable in several advanced usage such as nano-electronic and optoelectronic devices [13, 14]. The workers also tend towards the exploration about luminescence properties of Si quantum dots and also noticed about the effect on the optical properties of Si QD's by quantum confinement [15, 16].

Significant research has been conducted on Si quantum dots for enhancing solar cell efficiency. Noteworthy works include studies on improved solar cell efficiency using Si quantum dots by Hong-Chen et al. [17], surface modification of Si quantum dot-sensitized solar cells by Hyunwoong Seo et al. [18], and investigations on Si quantum dots by Anna Castaldo et al. [19]. Further, Hyunwoong Seo et al. [20] explored the effect of different compositions on the performance of Si quantum solar cells, while Marc Rüdiger [21] studied bifacial n-type silicon solar cells. Research on Si tandem solar cells by H. Heidarzadeh et al. [22], the photoresponse of silicon quantum dot nanostructures in Si-rich nitride films by Pei Ling Li et al. [23], and Si quantum dot structures and their applications by L. Shcherbyna et al. [24] also contribute valuable insights. Other notable works include studies on the structural and electroluminescent properties of Si quantum dots by Yunjun Rui et al. [25], theoretical modeling of thin-film silicon solar cells by Zeman et al. [26] and analysis of hydrogenated amorphous silicon solar cells by Rodríguez et al. [27]. Dietmar Kohler et al. [28] analyzed large defect clusters in multicrystalline Si solar cells, while Tripathi et al. [29] investigated amorphous and nanocrystalline Si films deposited via the filtered vacuum arc technique. Zhang et al. [30] studied colloidal Si quantum dots for high-efficiency photovoltaics, and Gu et al. [31] have examined the properties of phosphorus-boron co-doped Si quantum dots thin film. Sofronov et al. [32] focused on photoinduced mid-infrared interband light absorption and

photoconductivity in Ge/Si quantum dots, and Das and Sarkar [33] worked on Si nanowires for implications in heterojunction solar cells. Spruijtenburg et al. [34] have provided a fabrication guide for planar Si quantum dot heterostructures.

The current research focuses on the synthesis, as well as the structural, optical, and electrical characterization of Si quantum dots, fabricated at varying substrate temperatures at a constant ambient argon pressure.

2. EXPERIMENTAL DETAILS

2.1. Fabrication of Silicon quantum dots (Si-QDs) thin films

Silicon quantum dots (Si-QDs) thin films, with a uniform thickness of approximately 20 nm, were synthesized on quartz substrates using the Physical Vapor Deposition (PVD) method. Silicon chips served as the source material and were placed in a graphite crucible positioned within a vacuum chamber. The chamber was evacuated to a high vacuum level of 10^{-6} Torr using a turbo molecular pump to eliminate any contaminants. Subsequently, argon (Ar) gas was introduced into the chamber, maintaining a working pressure of 4 Torr. The substrate temperatures were regulated at three distinct levels—165 K, 135 K, and 115 K—using liquid nitrogen cooling to control the size and deposition rate of the Si-QDs. Once the deposition process was complete, thin films of Si-QDs with varying dot sizes were successfully formed on the quartz substrates. The thickness of the films was accurately measured using an Edward FTM-7 quartz crystal thickness monitor.

2.2. Structural Analysis

The amorphous nature of the synthesized Si-QDs was confirmed through X-ray diffraction (XRD) analysis performed with a Rigaku Ultima IV High-Resolution X-Ray Diffractometer (HRXRD), utilizing a copper (Cu) target as the radiation source with a wavelength of $\lambda=1.54056\text{\AA}$ ($\text{Cu-K}\alpha_1$). The scan range for XRD measurements spanned from 30° to 70° , with a scanning rate of 2° per minute, providing critical insight into the structural characteristics of the Si-QDs.

2.3. Morphological Studies

Field Emission Scanning Electron Microscopy (FESEM) and High-Resolution Transmission Electron Microscopy (HRTEM) were employed to investigate the surface morphology and size distribution of the quantum dots. These imaging techniques offered high-resolution visualizations, confirming the uniformity and nanoscale dimensions of the Si-QDs, which ranged between 3-7 nm in size, depending on

the substrate temperature.

2.4. Optical and Electrical Measurements:

The optical properties of the Si-QDs thin films were characterized using LAMBDA 365 UV-Visible spectroscopy. Absorption spectra were recorded to determine the optical band gap and evaluate the quantum confinement effects in the synthesized Si-QDs. For electrical conductivity measurements, silver paste was applied as a contact electrode on the thin films. The films were mounted onto a specialized metallic sample holder, where a high vacuum of 10^{-4} Torr was maintained during the measurements. Temperature-dependent DC conductivity was assessed using a Keithley Model-617 digital electrometer. The experimental setup involved a constant voltage applied across the thin films, while the current response was recorded as the temperature of the sample was incrementally increased from 308 K to 428 K in steps of 5 K. This systematic temperature variation allowed for the examination of the thermal activation energy

and semiconducting behavior of the Si-QDs thin films.

3. RESULTS AND DISCUSSION

FESEM Studies: The surface morphology of silicon quantum dots (Si-QDs) synthesized at varying substrate temperatures of 165 K, 135 K, and 115 K under a constant argon pressure of 4 Torr was investigated using Field Emission Scanning Electron Microscopy (FESEM). Figures 1 (a-b-c) present the FESEM images of Si-QDs deposited at these temperatures. It is observed that the quantum dots exhibit a spherical shape with an average size of approximately 5 nm. Notably, as the substrate temperature decreases, the size of the Si-QDs remains within a similar range, but there is a slight tendency for increased aggregation at higher temperatures. This aggregation suggests that the thermal energy available at higher temperatures facilitates a greater degree of surface diffusion and coalescence of quantum dots, leading to clustering.

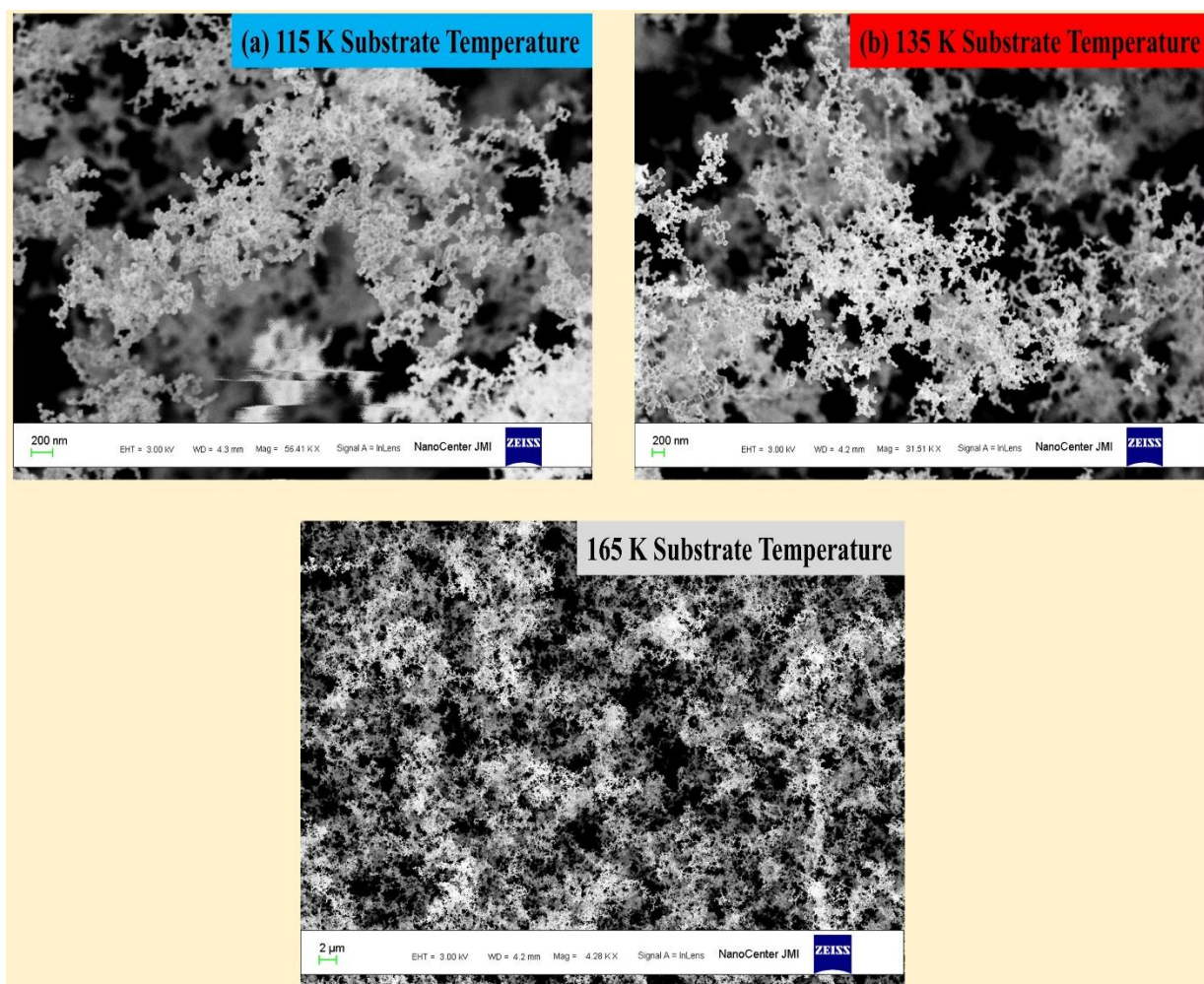


Fig. 1. (a-c): FESEM images of Si quantum dots prepared at substrate temperatures of 115 K, 135 K, and 165 K under 4 Torr Argon pressure.

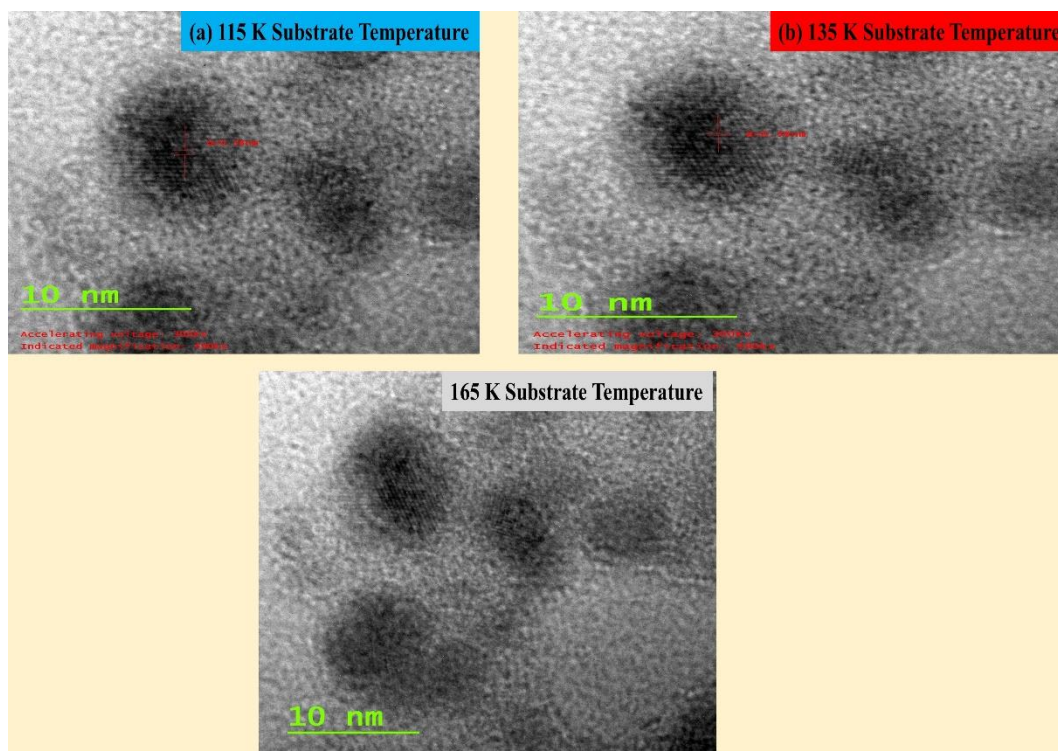


Fig. 2. (a-c): HRTEM images of Si quantum dots prepared at substrate temperatures of 115 K, 135 K, and 165 K under 4 Torr Argon pressure.

HRTEM Analysis: High-Resolution Transmission Electron Microscopy (HRTEM) images, displayed in Figures 2 (a-b-c), offer a more detailed examination of the size and arrangement of the Si-QDs synthesized at different substrate temperatures. The HRTEM results further corroborate the size range of the quantum dots, which varies between 3 to 7 nm. These nanodots are clearly distinguished in the images, though a degree of aggregation is visible, especially at higher substrate temperatures. This phenomenon could be attributed to the increased mobility of silicon atoms on the substrate surface at elevated temperatures, resulting in enhanced nucleation and growth of the quantum dots. The interparticle spacing of the Si-QDs, measured using HRTEM, reveals an average spacing of 0.36 nm for quantum dots deposited at 165 K, while the interspacing slightly increases to 0.37 nm for samples deposited at 135 K and 115 K. The increase in spacing at lower temperatures might suggest limited atomic mobility, preventing the coalescence of quantum dots and leading to a more isolated arrangement.

X-Ray Diffraction (XRD) Studies: The crystallographic structure of the Si-QDs was examined using X-ray diffraction (XRD), and the corresponding patterns are presented in Figure 3. The XRD analysis shows no distinct peaks for the quantum dots synthesized at any of the three substrate temperatures (165 K, 135 K, and 115 K), confirming their amorphous nature. The absence of crystalline peaks indicates that the Si-QDs did not exhibit long-range atomic order, which is typical for materials prepared at low temperatures

via physical vapor deposition (PVD). The amorphous structure is advantageous for optoelectronic applications, as it can result in unique electronic properties that differ from their bulk crystalline counterparts, such as a direct bandgap in nanostructures.

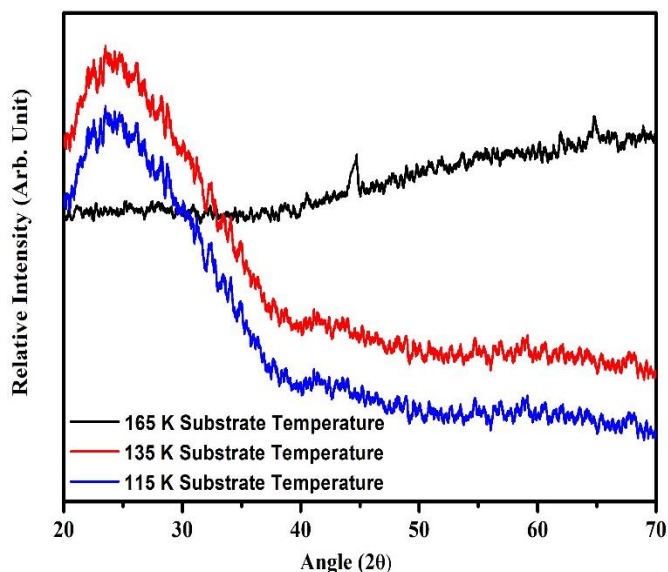


Fig. 3. HRXRD patterns of Si quantum dots prepared at substrate temperatures of 115 K, 135 K, and 165 K under 4 Torr Argon pressure.

Optical studies: Optical parameters of synthesized Silicon quantum dots at different substrate temperatures 165 K, 135 K and 115 K with fixed working pressure of 4 Torr have been determined within the wavelength span 400-900 nm. The optical density determined by UV-VIS spectrophotometer can be used to derive absorption coefficient (α) using the relation [35, 36].

$$\alpha = \text{Optical Density} / \text{Film Thickness} \quad (1)$$

We have calculated α (absorption coefficient) using the above equation and shown in Figure 4. It was observed that absorption increases exponentially with the rise in photon energy for all thin films. The quantum dots fabricated at a higher substrate temperature (165 K) exhibit greater absorption than those prepared at a lower substrate temperature (115 K and 135 K), which can be attributed to the more aggregation of quantum dots at higher substrate temperature. To calculate the optical band gap of a material, the following relation is used:

$$(\alpha h\nu)^{1/n} = B (h\nu - E_g) \quad (2)$$

where ν is the frequency of the incident beam, B is a constant, E_g is the optical band gap, and $1/n$ is an exponent. The value of $1/n$ can be taken as $1/2$, $3/2$, 2 , or 3 , depending on the electronic transitions responsible for absorption [37, 38]. The system of Silicon quantum dots follows the direct transition rule, where the extrema lie at the same point in k -space [39]. Based on this direct transition, the equation is rewritten as:

$$(\alpha h\nu)^2 \propto (h\nu - E_g) \quad (3)$$

The relationship between $(\alpha h\nu)^2$ and photon energy ($h\nu$) for Silicon quantum dots is shown in Figure 5. The energy gap values were calculated by determining the X-axis intercept of the $(\alpha h\nu)^2$ vs $(h\nu)$ plots. The calculated (E_g) values are presented in Table 1. The estimated optical band gap for quantum dots prepared at 115 K, 135 K and 165 K substrate temperatures are 3.10 eV, 3.32 eV, and 3.52 eV respectively. This increment in the optical band gap with increasing substrate temperatures is due to the increase in the quantum dot size, as confirmed by the FESEM and HRTEM micrographs.

The "density of states model" proposed by Mott and Davis appears to be the most appropriate method for explaining the observed increase in bandgap, as optical absorption is directly influenced by short-range orderings and defects associated with non-crystalline states [40]. According to this model, the disorders and defects in non-crystalline structures are determined by the extent of localized states near the mobility edges. The variation in bandgap can also be attributed to shifts in the Fermi level, which are linked to the distribution of electrons in localized states [41]. The slopes of the straight line plots provide Tauc's parameter (B^2), which is strongly affected by the nature of bonding. The increase in B^2 with rising substrate temperature suggests that, at higher substrate temperature, the chemical ordering in the synthesized quantum dots is more organized [42].

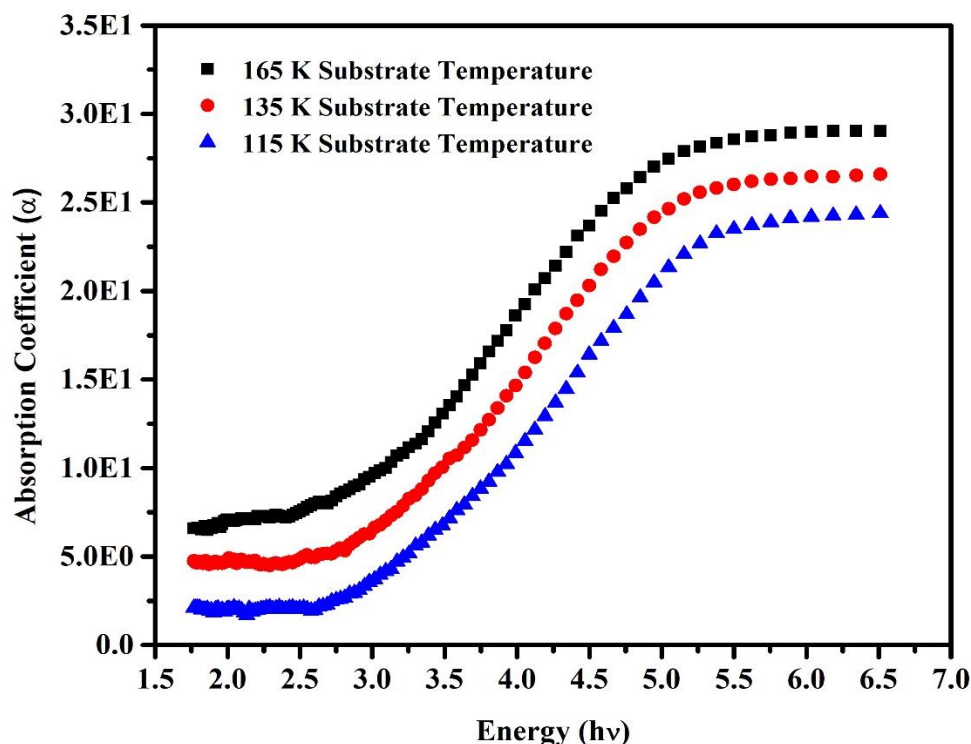


Fig. 4. Absorption coefficient as a function of energy for Si quantum dots prepared at substrate temperatures of 115 K, 135 K, and 165 K under 4 Torr Argon pressure.

Table 1. Optical and electrical parameters of synthesized Si quantum dots at different substrate temperatures under a constant Argon pressure of 4 Torr.

S. No.	Substrate temperature (K)	Absorption Coefficient (cm^{-1}) at $\lambda = 260 \text{ nm}$	Tauc's parameter (B^2)	Optical Band Gap E_g (eV)	σ_{DC} ($\Omega^{-1}\text{cm}^{-1}$) at $T=368 \text{ K}$	ΔE_c (eV)
1.	165	24.83×10^4	1.34	3.52	6.45×10^{-6}	0.45
2.	135	21.72×10^4	0.86	3.32	4.42×10^{-6}	0.43
3.	115	19.68×10^4	0.57	3.10	2.96×10^{-6}	0.40

Electrical studies: The study of transport phenomena in synthesized Silicon quantum dots can be effectively carried out through electrical transport studies [43]. Analyzing the electrical transport properties of a material is particularly important, as it provides a straightforward way to understand certain physical characteristics of the synthesized sample [44]. The dark conductivity (σ_{DC}) of Si quantum dots at different temperatures (T) can be determined using the Arrhenius Equation [45].

$$\sigma_{\text{DC}} = \sigma_0 \exp(-\Delta E_c / KT) \quad (4)$$

This equation can be written as:

$$\ln \sigma_{\text{DC}} = \ln \sigma_0 - (\Delta E_c / KT)$$

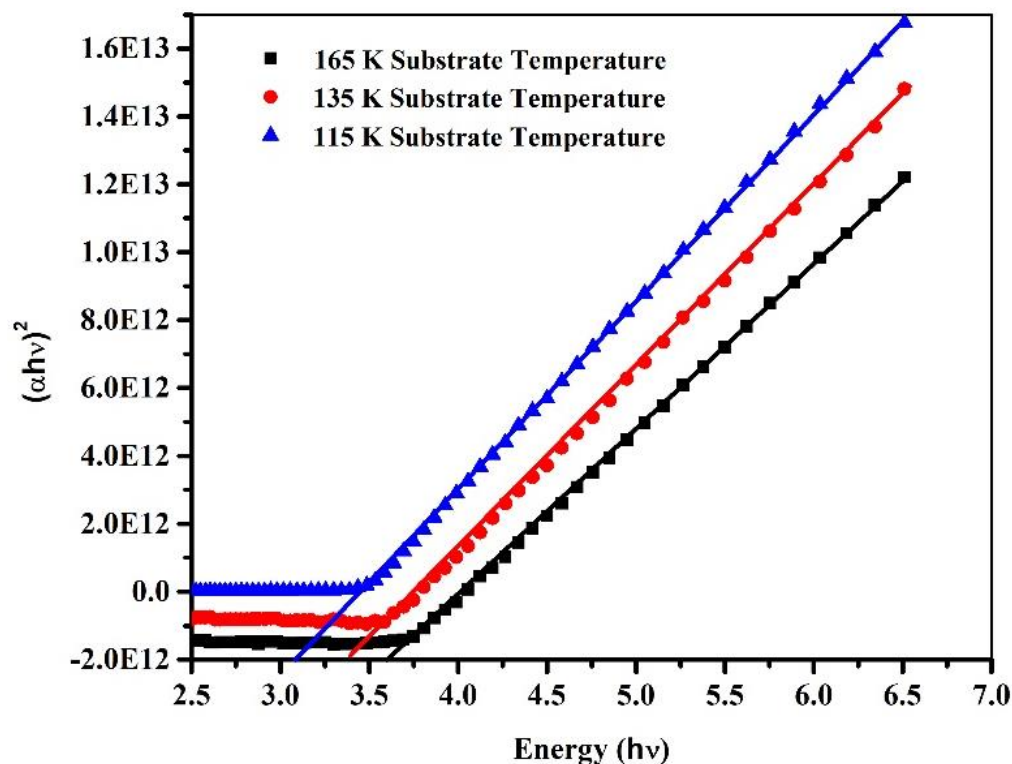
or, equivalently:

$$\ln \sigma_{\text{DC}} = -(\Delta E_c / 1000 \text{ K})(1000/T) + \ln \sigma_0 \quad (5)$$

This indicates a linear relationship between $\ln \sigma_{\text{DC}}$ and $1000/T$, with the slope of this line equal to $(\Delta E_c / 1000 \text{ K})$. The activation energy (ΔE_c) can be calculated using the relation:

$$\Delta E_c = 1000 \text{ K} \times \text{slope of straight line} \quad (6)$$

where K is Boltzmann's constant. DC conductivity measurements of the synthesized Si quantum dots at different substrate temperatures were performed within a temperature range of 298 K to 393 K (Figure 6).

**Fig. 5.** $(\alpha h\nu)^2$ vs. $h\nu$ (eV) for Si quantum dots prepared at substrate temperatures of 115 K, 135 K, and 165 K under 4 Torr Argon pressure.

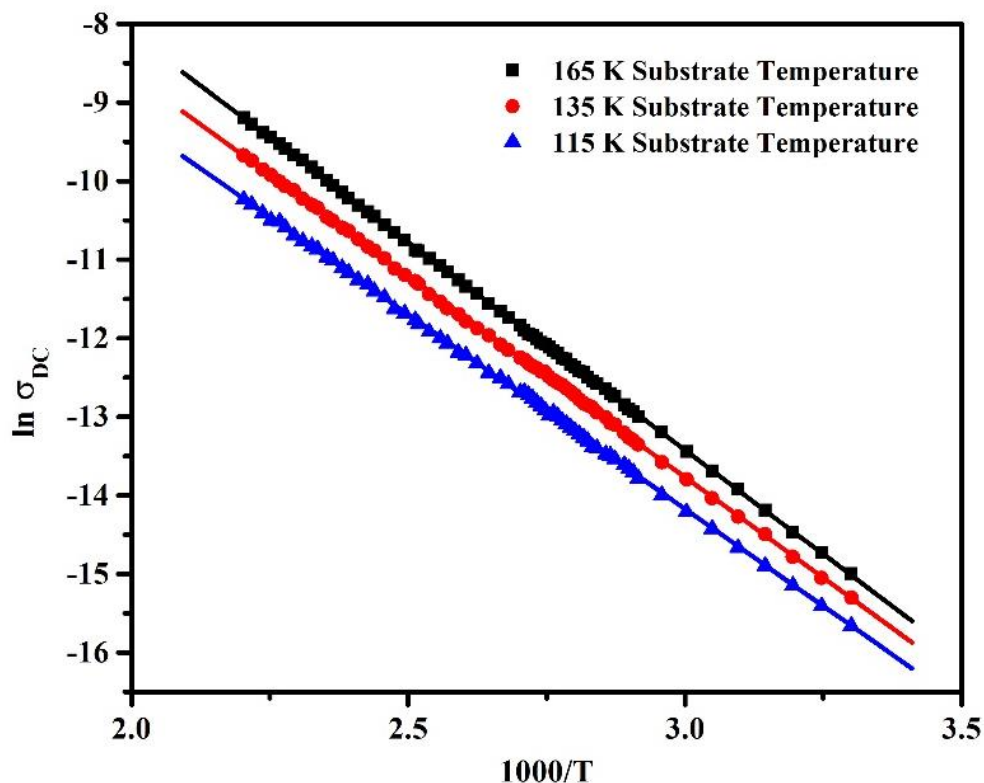


Fig. 6. Temperature dependence of dc conductivity in the range of 308 to 428 K for Si quantum dots prepared at substrate temperatures of 115 K, 135 K, and 165 K under 4 Torr Argon pressure.

The exponential increase in DC conductivity over this temperature range confirms the semiconducting nature of the prepared quantum dots. The estimated values of DC conductivity and activation energy at different substrate temperatures are listed in Table 1. The observed values suggest that the conduction mechanism in Si quantum dots is due to thermally-assisted charge carrier tunnelling within localized states of the band tails [46]. The slight increase in DC conductivity and activation energy with rising substrate temperatures can be attributed to a shift in the Fermi level [47] or an increased amount of hopping conduction via defect states [48].

4. CONCLUSION

In this study, we successfully synthesized and characterized silicon quantum dots (Si-QDs) with a focus on their structural, optical, and electrical properties. The morphological analysis via FESEM revealed the formation of Si-QDs with an average size ranging from 3 to 7 nm, a result corroborated by HRTEM imaging. These analyses confirmed the quantum confinement effects expected in such small nanostructures. The X-ray diffraction (XRD) studies further validated the amorphous nature of the Si-QDs synthesized at various substrate temperatures, which is a key characteristic for improving certain optoelectronic properties. The optical

studies demonstrated a notable increase in the bandgap energy with decreasing quantum dot size, attributed to the quantum confinement effect. This tunability of the bandgap is essential for optimizing the absorption characteristics of Si-QDs in optoelectronic devices, such as solar cells, where efficient light harvesting is critical. The shift in the optical bandgap as a function of temperature indicates that substrate temperature during synthesis directly influences the quantum dot size and, consequently, their optical properties. In terms of electrical properties, the Si-QDs exhibited a typical semiconducting behavior, with the DC conductivity (σ_{DC}) increasing exponentially as the temperature rose from 308 K to 428 K. This behavior suggests that charge transport in these materials occurs through an activated process, indicative of hopping conduction between localized states. The observed reduction in activation energy and the shift in the Fermi level at higher temperatures point to enhanced charge carrier mobility and a stronger percolation network in the more aggregated Si-QDs formed at elevated substrate temperatures. The findings from this research highlight the significant potential of Si-QDs for applications in optoelectronics, particularly in the field of solar energy conversion. The ability to control the size and aggregation of Si-QDs by varying substrate temperature allows for fine-tuning of both optical and electrical properties, making these materials promising candidates for the development of highly efficient, next-generation solar cells. Future work will focus on integrating these Si-QDs into device architectures and

exploring their performance under real-world conditions.

CONFLICT OF INTEREST

The authors declare that there is no conflict of interests.

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